

JetClip

200 mm RTP & RTCVD Cluster Tool

Si, SiGe Epitaxy Multi processing capability

The Jipelec JetClip is a SEMI-MESC compatible Rapid Thermal Processing cluster module for wafer sizes up to 200 mm diameter



The full metal-sealed, stainless steel chamber offers an ultra-clean environment for a large range of RTP and RTCVD processes.

The Quartz Lamp Heater Array is controlled by a Power Supply with input from a Pyrometer to give optimum control and repeatability.

A Robot handling Unit and Load-Lock are both available as option as are Stand Alone Systems.

Applications:

- RTA: annealing, implant monitoring
- RTO: Rapid Thermal Oxidation
- RTN: Rapid Thermal Nitridation
- RTD: Rapid Thermal Diffusion for spin-on dopants
- Intrinsic and doped
- Silicon and SiGe(C) Epitaxy
- Atmospheric pressure silicon deposition

Performance:

Temperature range:	ambient to 1200°C
Ramp rate:	1°C/s to 200°C/s
Pyrometer control:	250°C to 1200°C



Features:

- Up to 200 mm wafers
- Full metal sealed cold wall chamber
- Pyrometer temperature control
- Atmospheric & vacuum process capability
- One purge gas line
- Up to 12 gas lines with MFC
- High vacuum capability

Options:

- Turbomolecular pumping unit
- Load-lock for manual loading
- Quartz cassette up to 13 wafers
- Robot handling